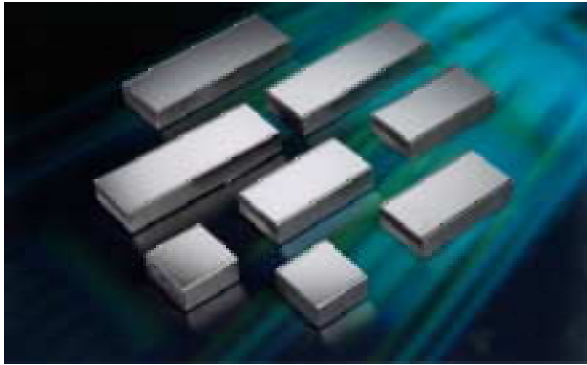


Parallel beam X-ray optics for CrK α , CoK α , CuK α , MoK α , AgK α radiation

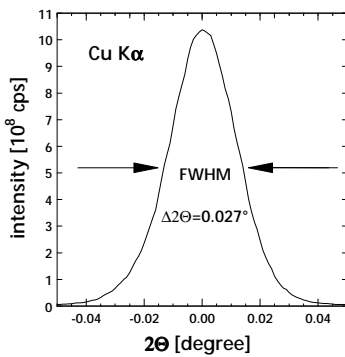


- Various parallel beam optics for single and twin mirror arrangements
- highest intensity and low divergence
 - no influence of sample surface position errors on peak position for reflectometry and diffractometry
 - superior K β suppression
 - sample fluorescence suppression
 - easy and fast sample alignment

Selected results for twin mirror arrangement:

cross intensity

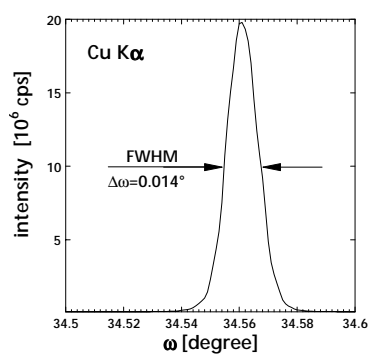
$I > 1.000.000.000$ cps



2θ -scan without sample

angle resolution

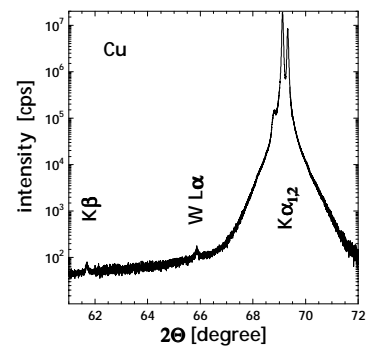
$\Delta\omega < 0.02^\circ$



rocking-scan Si(400)
silicon wafer

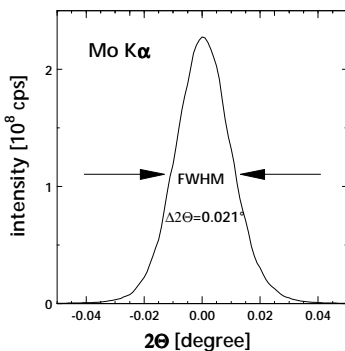
K β - suppression

$I_{\text{CuK}\alpha 1} : I_{\text{CuK}\beta} > 1.000.000 : 1$



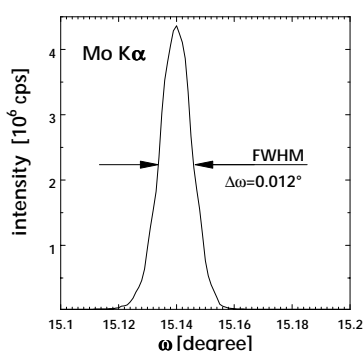
Θ - 2θ scan Si(400)
silicon wafer

$I > 200.000.000$ cps



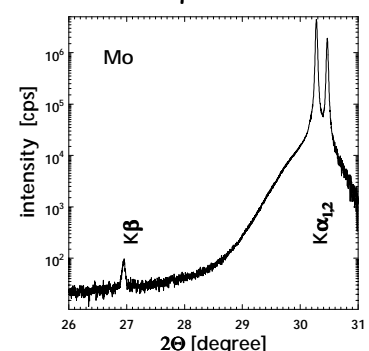
2θ -scan without sample

$\Delta\omega < 0.02^\circ$



rocking-scan Si(400)
silicon wafer

$I_{\text{MoK}\alpha 1} : I_{\text{MoK}\beta} > 100.000 : 1$



Θ - 2θ scan Si(400)
silicon wafer